EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	176	((119/837) or (606/164)).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT	OR	OFF	2007/12/14 09:45
L2	3	L1 and @pd>"20050202"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT	OR	OFF	2007/12/14 09:46
L3	3	"beak" and "bird" and "energy" and ("tongue" or "throat") and "aperture"	US-PGPUB	OR	OFF	2007/12/14 09:48
L4	9	"beak" and "bird" and "energy" and ("tongue" or "throat") and "aperture"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT	OR	OFF	2007/12/14 09:54
L5	46	"452"/\$.ccls. and "beak"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT	OR	OFF	2007/12/14 09:55

10702369_CLS.txt Most frequently occurring classifications of patents returned from a search Of 10702369 on Dec 14 , 2007

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Original Classifications
8 606/164
3 438/297
2 119/464
2 119/715
2 438/241
2 119/72.5

Cross-Reference Classifications
4 257/506
3 438/440
3 257/E21.258
2 257/E21.339
2 257/E21.564
2 257/648
2 438/298
2 219/384
2 438/294

Combined Classifications
8 606/164
4 438/297
4 257/506
3 438/440
3 119/464
3 119/715
3 257/E21.258
2 257/E21.339
2 257/E21.339
2 257/E21.564
2 119/537
2 438/241
2 257/648
2 438/298
2 119/537
2 438/241
2 257/648
2 438/298
2 219/384
2 438/298
2 119/468
2 438/294
2 119/72.5
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10702369_LIST.txt

PLUS Search Results for S/N 10702369 Searched Dec 14, 2007. The Patent Linguistic Utility System (PLUS) is a USPTO automated search system for U.S. Patents from 1971 to present. PLUS is a query-by-example search system which produces a list of patents that are most closely related linguistically to the application searched. This search was prepared by the staff of the Scientific and Technical Information Center, SIRA. **RE31202**

10702369_QUAL.txt

200501155 7232450		99
7232450 200401432 4343310 5182226	92	92
5182226 5391907 4343309	83 83 83	
4343309 4627384	83 83 83	
4627384 4913676 5235934 5651731	83	
5651731 5722936	83 83	
5722936 5758596 4352236 4026289	83 78	
4951610	78 78	
5836267 4375814	78 78	
RE31202 4395973	78 78	
4446819 4551910	78 78	
4612701 4762805	78 78	
5022345	78 78 78	
5588397	78	
5676001	78 78	
5677234 6133087 6136651	78 78	
6136651 6140670 6187645	78 78	
6332431	78 78	
6468870 200401122	78 299	78
4558662 5301635	75 75 75	
5494000 5894813	75 75 73	
5455438 4394181	73	
3807360 4040425	69 69	
4437432 4949327	69 69	
5250298 5346421	69 69	
5393693	69	

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10702369_CLSTITLES.txt
Titles of most frequently occurring classifications of patents returned
     from a search of 10702369 on Dec 14, 2007
                    (8 OR, 0 XR)
     606/164
          Class 606
                         SURGERY
          606/1
                         .INSTRUMENTS
          606/163
                         .. Means for debeaking or dehorning animals
          606/164
                         ...By electrical or thermal application
                    (3 OR, 1 XR)
     438/297
          Class 438
                         SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
                         .MAKING FIELD EFFECT DEVICE HAVING PAIR OF ACTIVE REGIONS
          438/142
SEPARATED BY GATE STRUCTURE BY FORMATION OR ALTERATION OF SEMICONDUCTIVE ACTIVE
REGIONS
                         .. Having insulated gate (e.g., IGFET, MISFET, MOSFET, etc.)
          438/197
                         ...Including isolation structure
....Recessed oxide formed by localized oxidation (i.e.,
          438/294
          438/297
LOCOS)
  4 257/506
                    (0 \text{ OR}, 4 \text{ XR})
          Class 257
                         ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE
DIODES)
          257/499
                         INTEGRATED CIRCUIT STRUCTURE WITH ELECTRICALLY ISOLATED
COMPONENTS
          257/506
                         ..Including dielectric isolation means
                    (0 \text{ OR}, 3 \text{ XR})
     438/440
          Class 438
                         SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
                         .FORMATION OF ELECTRICALLY ISOLATED LATERAL SEMICONDUCTIVE
          438/400
STRUCTURE
          438/439
                         .. Recessed oxide by localized oxidation (i.e., LOCOS)
          438/440
                         ...Including nondopant implantation
     119/464
                    (2 OR, 1 XR)
          Class 119
                         ANIMAL HUSBANDRY
          119/416
                         .CONFINING OR HOUSING
          119/452
                         ..Animal display or open work enclosure (e.g., cage, etc.)
          119/459
                         ...Bird cage
                         ....With feeding or watering means
          119/464
          (2 OR, 1 XR)
Class 119 ANTW
    119/715
                         ANIMAL HUSBANDRY
                         .ANIMAL CONTROLLING OR HANDLING (E.G., RESTRAINING,
          119/712
BREAKING, TRAINING, SORTING, CONVEYING, ETC.)
           119/713
                         ..Bird
           119/714
                         ...Body worn
           119/715
                         ....Head carried
  3 257/E21.258 (0 OR, 3 XR) Class 257 ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE
DIODES)
                          .PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR
           257/E21.001
TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF PARTS THEREOF (EPO)
                         .. Manufacture or treatment of semiconductor device (EPO)
           257/E21.002
                         ...Device having at least one potential-jump barrier or
           257/E21.04
surface barrier, e.g., PN junction, depletion layer, carrier concentration layer
(EPO)
                         ....Device having semiconductor body comprising Group IV
elements or Group III-V compounds with or without impurities, e.g., doping materials
(EPO)
                         .....Treatment of semiconductor body using process other
           257/E21.211
than deposition of semiconductor material on a substrate, diffusion or alloying of
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10702369_CLSTITLES.txt
impurity material, or radiation treatment (EPO) 257/E21.214 .....To change their s
                            .....To change their surface-physical characteristics or
shape, e.g., etching, polishing, cutting (EPO) 257/E21.24 .....To form insulat
                           .....To form insulating layer thereon, e.g., for masking
or by using photolithographic technique (EPO)
                            ........Using masks (EPO)
           257/E21.258
  2 257/E21.339 (0 OR, 2 XR)
Class 257 ACTIVE
                           ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE
DIODES)
                            .PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR
           257/E21.001
TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF PARTS THEREOF (EPO) 257/E21.002 ... Manufacture or treatment of semiconductor device
                           .. Manufacture or treatment of semiconductor device (EPO)
           257/E21.04
                           ...Device having at least one potential-jump barrier or
surface barrier, e.g., PN junction, depletion layer, carrier concentration layer
(EPO)
257/E21.085 ....Device having semiconductor body comprising Group IV elements or Group III-V compounds with or without impurities, e.g., doping materials
(EPO)
                            .....Radiation treatment (EPO)
           257/E21.328
                           .....With high-energy radiation (EPO)
.....Producing ions for implantation (EPO)
.....In Group IV semiconductor (EPO)
            257/E21.331
           257/E21.334
           257/E21.335
                            ......of electrically inactive species in silicon to make
            257/E21.339
buried insulating layer (EPO)
           Class 257 ACT XR
  2 257/E21.564
                           ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE
DIODES)
            257/E21.001
                            .PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR
TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF PARTS THEREOF (EPO) 257/E21.532 ...manufacture or treatment of devices consisting o
                           .. Manufacture or treatment of devices consisting of
plurality of solid-state components formed in or on common substrate or of parts
thereof; manufacture of integrated circuit devices or of parts thereof (EPO)
                            ...Manufacture of specific parts of devices (EPO)
            257/E21.536
                            ....Making of isolation regions between components (EPO)
            257/E21.54
                            .....Dielectric regions, e.g., EPIC dielectric isolation,
            257/E21.545
LOCOS; trench refilling techniques, SOI technology, use of channel stoppers (EPO)
           257/E21.561
                           ......Using semiconductor or insulator technology, i.e., SOI
technology (EPO)
                            ......SOI together with lateral isolation, e.g.,
            257/E21.564
local oxidation of silicon, or dielectric or polycrystalline material refilled
trench or air gap isolation regions, e.g., completely isolated semiconductor
islands (EPO)
                      (1 OR, 1 XR)
     119/537
           Class 119
                           ANIMAL HUSBANDRY
            119/416
                            .CONFINING OR HOUSING
                            ..Portable or nonconfined bird perch
            119/537
                      (2 OR, 0 XR)
     438/241
            Class 438
                            SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
            438/142
                            .MAKING FIELD EFFECT DEVICE HAVING PAIR OF ACTIVE REGIONS
SEPARATED BY GATE STRUCTURE BY FORMATION OR ALTERATION OF SEMICONDUCTIVE ACTIVE
REGIONS
                            .. Having insulated gate (e.g., IGFET, MISFET, MOSFET, etc.)
            438/197
                            ...Including passive device (e.g., resistor, capacitor,
            438/238
etc.)
           438/239
438/241
                            ....Capacitor
                            .....And additional field effect transistor (e.g., sense or
access transistor, etc.)
  2 257/648
                      (0 \text{ OR}, 2 \text{ XR})
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10702369_CLSTITLES.txt
                         ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE
          Class 257
DIODES)
          257/629
                         .WITH MEANS TO CONTROL SURFACE EFFECTS
          257/632
                         ...Insulating coating
                         ...Insulating layer recessed into semiconductor surface
          257/647
(e.g., LOCOS oxide)
                         ....Combined with channel stop region in semiconductor
          257/648
  2 438/298
                    (0 \text{ OR}, 2 \text{ XR})
          Class 438
                         SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
          438/142
                         .MAKING FIELD EFFECT DEVICE HAVING PAIR OF ACTIVE REGIONS
SEPARATED BY GATE STRUCTURE BY FORMATION OR ALTERATION OF SEMICONDUCTIVE ACTIVE
REGIONS
                         ..Having insulated gate (e.g., IGFET, MISFET, MOSFET, etc.)
          438/197
          438/294
                         ...Including isolation structure
                         ....Recessed oxide formed by localized oxidation (i.e.,
          438/297
LOCOS)
                         .....Doping region beneath recessed oxide (e.g., to form
          438/298
chanstop, etc.)
    219/384
                   (0 \text{ OR}, 2 \text{ XR})
          Class 219
                         ELECTRIC HEATING
          219/200
                         .HEATING DEVICES
          219/383
                         ..Electric arc-type devices
          219/384
                         ...with perforating or disintegrating means
          Class 438
    438/452
                         SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
          438/400
                         .FORMATION OF ELECTRICALLY ISOLATED LATERAL SEMICONDUCTIVE
STRUCTURE
                         .. Recessed oxide by localized oxidation (i.e., LOCOS)
          438/439
          438/452
                         ...Plural oxidation steps to form recessed oxide
                    (1 OR, 1 XR)
     119/468
          Class 119
                         ANIMAL HUSBANDRY
          119/416
                         .CONFINING OR HOUSING
          119/452
                         ..Animal display or open work enclosure (e.g., cage, etc.)
          119/459
                         ...Bird cage
                         ....With attachment device
          119/467
                         ....Perch for cage
          119/468
    438/294
                    (0 \text{ OR}, 2 \text{ XR})
          Class 438
                         SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
          438/142
                         .MAKING FIELD EFFECT DEVICE HAVING PAIR OF ACTIVE REGIONS
SEPARATED BY GATE STRUCTURE BY FORMATION OR ALTERATION OF SEMICONDUCTIVE ACTIVE
REGIONS
                         ...Having insulated gate (e.g., IGFET, MISFET, MOSFET, etc.)
          438/197
          438/294
                         ...Including isolation structure
                    (2 OR, 0 XR)
     119/72.5
          Class 119
                         ANIMAL HUSBANDRY
          119/72
                         .WATERING OR LIQUID FEED DEVICE
          119/72.5
                         ..Drop-delivering
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